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Supporting Information

Vertical oriented MoS₂/Si heterojunction for ultrahigh and ultrafast photoresponse photodetector

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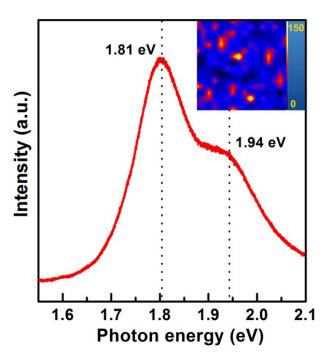
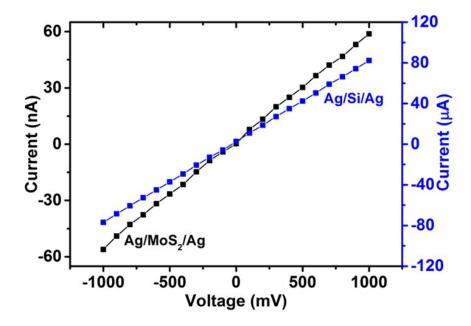


Fig. S1 PL spectra of the V-MoS₂ nanosheets with inset the PL mapping result.



 $\textbf{Fig. S2} \ \text{The I-V curves for the Ag/MoS}_2/\text{Ag structure and the Ag/Si/Ag structure, respectively.}$

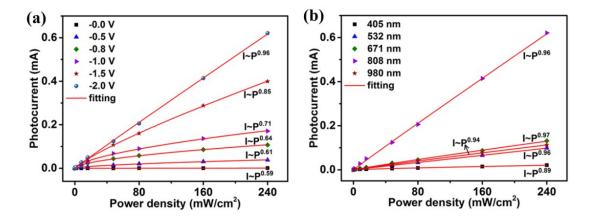


Fig. S3 (a) Photocurrent as a function of incident laserdensity at bias of 0 V, -0.5 V, -0.8 V, -1.0 V, -1.5 V, and -2 V. (b) Photocurrent as a function of incident laser density at bias of -2 V for different laser wavelengthes.

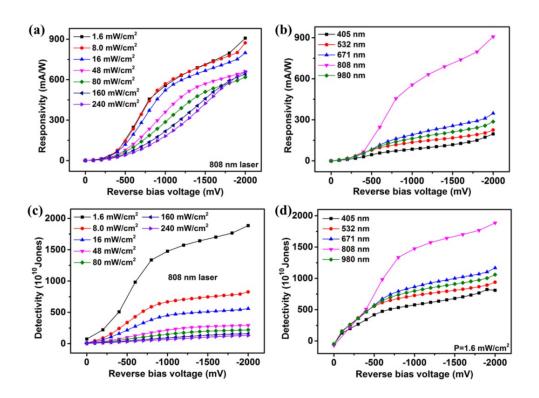


Fig. S4 Responsivity as a function of reverse bias voltage (a) under different illumination densities for 808 nm laser, and (b) under different wavelengthes with illumination density of 1.6 mW/cm². Detectivity as a function of reverse bias voltage (c) under different illumination densities for 808 nm laser, and (d) under different wavelengthes with illumination density of 1.6 mW/cm².

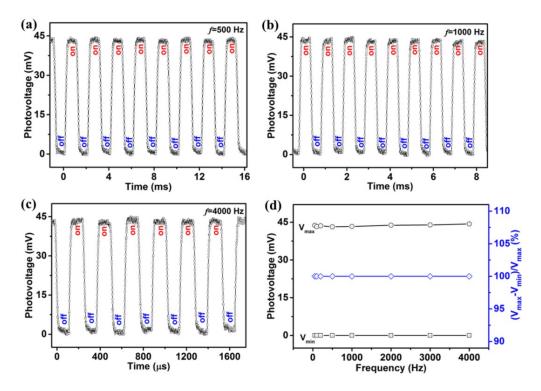
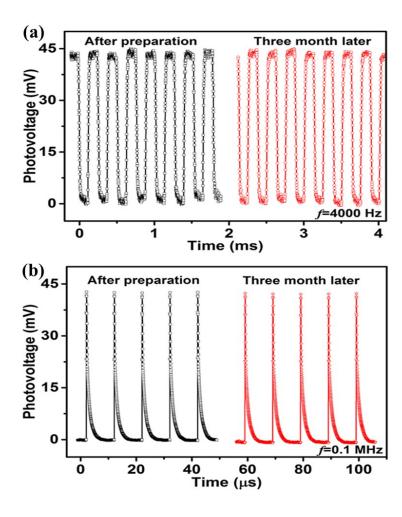


Fig. S5 Time-dependent photovoltages at frequencies of (a) 500 Hz, (b) 1000 Hz, and (c) 4000 Hz. (d) V_{max} , V_{min} , and relative balance (V_{max} - V_{min})/ V_{max} as a function of chopper frequency.



Fi. S6 Time-dependent photovoltages of the as-fabricated device and the same device after storage in air for three months under laser pulse frequency of (a) 4000 Hz (by chopper), and (b) 0.1 MHz (by fs-width laser).